

ABSTRACT

A lithographic projection apparatus comprising: a radiation system for providing a projection beam of radiation; a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern; a substrate table for holding a substrate; a projection system for projecting the patterned beam onto a target portion of the substrate; an illumination system for conditioning said beam of radiation beam so as to provide a conditioned radiation beam so as to be able to illuminate said patterning means; and a beam delivery system comprising redirecting elements for redirecting and delivering said projection beam from said radiation system to said illumination system. The radiation beam is arranged to have a predetermined polarization state and said redirecting elements are arranged to provide a minimum radiation loss in relation to said predetermined polarization state of said radiation beam.